

Ion Source

IS 100

The IS 100 is an extractor type ion source ideally suited for sample or STM tip sputtering

I direct gas inlet

I reactive gas sputtering

I adjustable flange-sample distance

I for sample cleaning

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IS 100 Ion Source

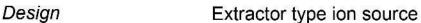
The IS 100 is an extractor type ion source ideally suited for sample sputtering or STM tip cleaning.

The low cost and sturdy design guarantees stable operating conditions over a long period of time.

The Yttrium coated Iridium cathode allows for noble and reactive gas operation.

High emission currents are provided even at low beam energies, with the primary energy range reaching from 0.2 to 5 keV and working pressures in the range of 10⁻⁵ - 10⁻⁶ mbar (direct gas inlet).

Spot size and current density depend on the distance between source and sample, where the overall length of the IS 100 can be selected to meet the specific requirements of the used UHV chamber.



Primary energy range 0.2 - 5 keV
 Total current 15 - 20 μA
 Working pressure 10⁻⁵-10⁻⁶mbar

Spot size (FWHM) > 4 mm (at > 50 mm working distance

and 5 kV)

Mounting flange DN 35 CF

Insertion depth variable

Working distance variable

Bakeable up to 250°C

energy range 0.2 - 5 keV

medium spot size (ca. 4-12 mm)

► reactive gas sputtering

▶ efficient sample cleaning

Related products:

IS 200 Ion Source, 0.2 - 3 kV, XY-deflection, focus unit IS 300 Ion Source, 0.2 - 5 kV, XY-deflection, focus unit

PS-IS 200 Power Supply

Display lon energy

Dimension (W x H x D) 19" x 133 mm x 415 mm



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